

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of : Ismail Kashkoush et al.  
Serial No. : 10/585,229  
Filed : April 20, 2007  
Title: SYSTEM AND METHOD FOR SELECTIVE ETCHING OF SILICON  
NITRIDE DURING SUBSTRATE PROCESSING  
Art Unit : 1713  
Examiner : Lan Vinh  
Attorney Docket: : AKR-034-US  
Confirmation No. : 9361

**AMENDMENT UNDER 37 C.F.R. § 1.312 (ACCOMPANYING ISSUE FEE)**

This Amendment is being submitted contemporaneously with the payment of the Issue Fee under 37 C.F.R. § 1.312. It is respectfully requested that the amendments set forth herein be accepted and entered in this case prior to issuance. The amendments are made to formalize the drawings. The amendments do not affect the allowed substance of the claim scope.

It is further requested that the subject application issue with the enclosed formal drawings.

**Amendments to the Drawings** begin on page 2 of this paper.

**Remarks** begin on page 3 of this paper.